

μ**ΕΤΟΗ ΕΟ-2000**Microetch Controller



Description

The $\mu ETCH$ EC-2000 provides accurate, reliable control for all copper microetching processes. The $\mu ETCH$ EC-2000 controls total copper removal by replenishing fresh microetch solution based on copper concentration. The $\mu ETCH$ EC-2000 allows the manufacturer to maximize copper loading and minimize operating costs.

Features	Benefits
Steady state process	Increases uptime and improves process capability
In-tank or flow-through sensor options	Optimize performance based on immersion or conveyorized application
High quality process instrumentation	Accurate, reliable process control
Optional degasser	Improves control of peroxide/sulfuric microetches
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